

	JST (UTC + 9) Japan Time	CST (UTC+8) China Time	CET (UTC + 1) Central Europe Time	PST (UTC - 8) California Time
	18/Jan./2022 12:30	18/Jan./2022 11:30	18/Jan./2022 04:30	17/Jan./2022
Opening remarks	13:00-13:10	12:00-12:10	05:00-05:10	20:00-20:10
key note lecture (1) Semiconductor Industries: Creating the opportunities for the bright future in Japan	13:10-13:50	12:10-12:50	05:10-05:50	20:10-20:50
key note lecture (2) Future Semiconductor Manufacturing Technology for Ultra-Smart Society	13:50-14:30	12:50-13:30	05:50-06:30	20:50-21:30
Invited speaker (1) The recent progress of SSMB EUV light source project at Tsinghua University	14:30-15:00	13:30-14:00	06:30-07:00	21:30-22:00
Break	15:00-15:20	14:00-14:20	07:00-07:20	22:00-22:20
Invited speaker (2) Demonstration of Proof-of-Concept of EUV and Beyond EUV FELs for Future Lithography	15:20-15:50	14:20-14:50	07:20-07:50	22:20-22:50
Invited speaker (3) Progress of DUV • EUV Light Source and its Extension to Leading Edge Semiconductor Manufacturing	15:50-16:20	14:50-15:20	07:50-08:20	22:50-23:20
Invited speaker (4) Challenge of attenuated phase shift mask for EUV lithography	16:20-16:50	15:20-15:50	08:20-08:50	23:20-23:50
Closing address & Photo-session	16:50-17:00	15:50-16:00	08:50-09:00	23:50-24:00

Sunao Ishihara

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